

Dominant recombination center in electron-irradiated 3C SiC

Son N.T., Sorman E., Chen W.M., Singh M., Hallin C., Kordina O.,
Monemar B., Janzen E., Lindstrom J.L.

Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden; National
Defence Research Institute, P.O. Box 1165, S-581 11 Linköping, Sweden; Department of Physics,
University of Hanoi, 90 Nguyen Trai, Hanoi, Viet Nam; Asea Brown Boveri Corporate Research, S-721 78
Västerås, Sweden

Abstract: Deep level defects and their role in carrier recombination processes in electron-irradiated 3C SiC have been studied by photoluminescence (PL) and optically detected magnetic resonance (ODMR). An isotropic ODMR spectrum, with a g value of 2.0061 ± 0.0002 and an effective electron spin $S=1/2$, is observed in irradiated 3C SiC films. From the spectral dependence studies of the ODMR signal, the defect is shown to be a deep level center related to a radiation-induced PL band with a zero-phonon line at 1.121 eV. Due to the competition between different carrier recombination channels, this ODMR spectrum can also be observed as a decrease of any other PL emissions from the sample, indicating its dominant role in recombination processes. © 1996 American Institute of Physics.

Year: 1996

Source title: Journal of Applied Physics

Volume: 79

Issue: 7

Page : 3784-3786

Cited by: 22

Link: Scopus Link

Correspondence Address: Son, N.T.; Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden; email: Son@ifm.liu.se

ISSN: 218979

CODEN: JAPIA

Language of Original Document: English

Abbreviated Source Title: Journal of Applied Physics

Document Type: Article

Source: Scopus

Authors with affiliations:

1. Son, N.T., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden, Department of Physics, University of Hanoi, 90 Nguyen Trai, Hanoi, Viet Nam
2. Sörman, E., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden
3. Chen, W.M., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden
4. Singh, M., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden

5. Hallin, C., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden
6. Kordina, O., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden, Asea Brown Boveri Corporate Research, S-721 78 Västerås, Sweden
7. Monemar, B., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden
8. Janzén, E., Dept. of Phys. and Msrmt. Technology, Linköping University, S-581 83 Linköping, Sweden
9. Lindström, J.L., National Defence Research Institute, P.O. Box 1165, S-581 11 Linköping, Sweden

References:

1. De Balona, L.A.S., Loubser, J.H.N., (1970) J. Phys. C, 3, p. 2344
2. Itoh, H., Yoshikawa, M., Nashiyama, I., Misawa, S., Okumura, H., Yoshida, S., (1990) IEEE Trans. Nucl. Sci., 37, p. 1732
3. Itoh, H., Hayakawa, N., Nashiyama, I., Sakuma, E., (1989) J. Appl. Phys., 66, p. 4529
4. Itoh, H., Yoshikawa, M., Nashiyama, I., Misawa, S., Okumura, H., Yoshida, S., (1992) J. Electron. Mater., 21, p. 707
5. Itoh, H., Yoshikawa, M., Nashiyama, I., Misawa, S., Okumura, H., Yoshida, S., (1993) Inst. Phys. Conf. Ser., 137, p. 255
6. Nagesh, V., Farmer, J.W., David, R.F., Kong, H.S., (1987) Appl. Phys. Lett., 50, p. 1138
7. Choyke, W.J., (1977) Inst. Phys. Conf. Ser., 31, p. 58. , and references therein
8. Dang, L.S., Lee, K.M., Watkins, G.D., Choyke, W.J., (1980) Phys. Rev. Lett., 45, p. 390
9. Romanov, N.G., Vetrov, V.A., Baranov, P.G., (1986) Sov. Phys. Semicond., 20, p. 96
10. Kennedy, T.A., Freitas, J.A., Bishop, S.G., (1990) J. Appl. Phys., 68, p. 6170
11. Kordina, O., Björketun, L.-O., Henry, A., Hallin, C., Glass, R.C., Huitman, L., Sundgren, J.E., Janzén, E., J. Cryst. Growth (in Press)
12. Choyke, W.J., Feng, Z.C., Powell, J.A., (1988) J. Appl. Phys., 64, p. 3163
13. Lin-Chung, P.J., Li, Y., (1986) Mater. Sci. Forum, 10-12, p. 1247
14. Ioth, H., Yoshikawa, M., Nashiyama, I., Okumura, H., Misawa, S., Yoshida, S., (1995) J. Appl. Phys., 77, p. 837